

# NEWS RELEASE

**Hitachi High-Tech**

**HITACHI**

**Hitachi High-Technologies Corporation**

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## Hitachi High-Tech and FEI Settle Patent Infringement Cases

Hitachi High-Technologies Corporation announced today that it had settled its dispute with FEI Company regarding Hitachi's patents relating to Focused Ion Beam (FIB) apparatus. To resolve various patent infringement cases raised by Hitachi, FEI desired to obtain licenses under Hitachi's FIB related patents, and Hitachi agreed to grant such licenses based on its judgment that two parties' negotiation resulted in reasonable and acceptable settlement terms. Subject to the terms of the agreement, Hitachi will dismiss all currently pending claims in the legal and administrative proceedings. The financial structure of the agreement consists of a one-time payment by FEI of \$15 million, and the framework of the agreement is cross license. The other specific terms of the settlement are confidential.

Hitachi High-Technologies considers its intellectual property rights as extremely important resources, and will continue to make every effort to protect such rights.

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